

PLEASE AMEND THE SPECIFICATION AS FOLLOWS:

After the title, insert--

This is a continuation of Patent Application serial number 09/557,395. Filing date 04/24/2000, A Method Integrating Low-K Materials in Semiconductor Fabrication, assigned to the same assignee as the present invention.

In the paragraph entitled "Field of the Invention" please make the grammatical correction as shown.

1) Field of the Invention

This invention relates generally to fabrication of a semiconductor device and more particularly to a method for forming low-K dielectric layers with improved thermal stability and structural strength by forming pillars, comprising material with good thermal stability and structural strength within the low-K dielectric layer.